## 10/586810 IAP11 Rec'd PCT/PTO 21 JUL 2006

## INFORMATION DISCLOSURE STATEMENT TRANSMITTAL

To Commissioner For Patents

Enclosed herewith is a Form PTO-1449, any required copies of documents listed thereon, and any concise explanation of their relevance is indicated below per 37 CFR 1.97.

Application Number	
Filing Date	
First Named Inventor	MEUNIER-BEILLARD, PHILIPPE
Group Art Unit	
Examiner Name	
Atty. Docket Number	US04 0056 US2

	U.S. PATENT DOCUMENTS				
Examiner Initials*	Cite No.1	Document Number NoKind Code <sup>2</sup> ( <i>if known</i> )	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns Lines, Where Relevant Passages or Relevant Figures Appear
	1	US- 5 506 427	04/09/1996	IMAI ET AL.	·
	2	us- 5 773 350	06/30/1998	HERBERT ET AL.	
		US-			

FOREIGN PATENT DOCUMENTS						
Examiner Initials*	Cite No.1	Document Number (ctry³-no.⁴-kind⁵, if known)	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of cited document	Pages, Columns Lines, Where Relevant Passages or Relevant Figures Appear	T <sup>6</sup>
	1	JP 02 203533	10/26/1990	TOSHIBA CORP		
	2	JP 02 205033	10/26/1990	HITACHI LTD		

NON-PATENT LITERATURE DOCUMENTS					
Cite No.1	Include name of the author (in capital letters), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.	T <sup>®</sup>			
1	DONKER J. J. T. M.: "VERTICAL PROFILE OPTIMISATION OF A SELF-ALIGNED SIGEC HBT PROCESS WITH AN n-CAP EMITTER"; BIPOLAR/BICMOS CIRCUIT AND TECHNOLOGY MEETING 2003; PP 111-114.				
2	P. D. AGNELLO: "GROWTH RATE ENHANCEMENT OF HEAVY n- AND p-TYPE DOPED SILICON DEPOSITED BY ATMOSPHERIC-PRESSURE CHEMICAL VAPOR DEPOSITION AT LOW TEMPERATURE"; JOURNAL ELECTROCHEM SOCIETY VOL. 140 NO. 9; 1993 PP 2703.				
	1	Cite No. Include name of the author (in capital letters), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.  1 DONKER J. J. T. M.: "VERTICAL PROFILE OPTIMISATION OF A SELF-ALIGNED SIGEC HBT PROCESS WITH AN n-CAP EMITTER"; BIPOLAR/BiCMOS CIRCUIT AND TECHNOLOGY MEETING 2003; PP 111-114.  2 P. D. AGNELLO: "GROWTH RATE ENHANCEMENT OF HEAVY n- AND p-TYPE DOPED SILICON DEPOSITED BY ATMOSPHERIC-PRESSURE CHEMICAL VAPOR DEPOSITION AT LOW			

Examiner	/John Doido/	Date	. 04/30/2009
Signature	/John Doyle/ 	Considere	1   04/30/2003

<sup>\*</sup> EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

<sup>&</sup>lt;sup>1</sup> Unique citation designation number. <sup>2</sup> See attached Kinds of U.S. Patent Documents. <sup>3</sup> Enter Office that issued the document, by the two-letter code (WIPO Standard ST.3). <sup>4</sup> For Japanese patent documents, the indication of the year of the reign of the Emperor must precede the serial number of the